

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Masuda et al.
Appl. No.	:	10/568,126
Filed	:	February 14, 2006
For	:	POSITIVE PHOTORESIST COMPOSITION AND RESIST PATTERN
Examiner	:	Chu, John S Y.
Group Art Unit	:	1752

**AMENDMENT AND RESPONSE TO OFFICE ACTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **June 27, 2007**, please consider the following amendments and remarks:

**Amendments to the claims** are reflected in the listing of claims which begin on page 2 of this paper.

**Remarks/Arguments** begin on page 4 of this paper.